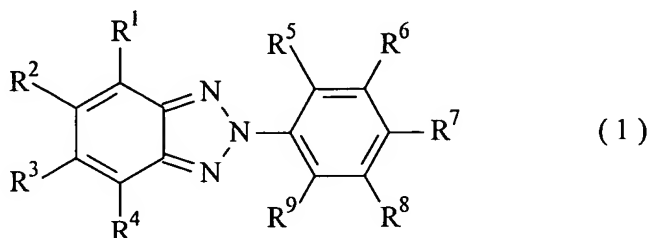


# CLAIMS

1. An improver for adhesion of a photosensitive resin composition to a substrate, which consists of an N-phenyl-2H-benzotriazole compound represented by the general formula (1):



wherein  $R^1$  to  $R^4$  each independently represent a hydrogen atom, a halogen atom or a  $C_{1-5}$  alkyl group;  $R^5$  to  $R^9$  each independently represent a hydrogen atom, a hydroxyl group, a  $C_{1-10}$  alkyl group, an aryl group, a  $C_{7-12}$  aralkyl group,  $-R^{10}COOR^{11}$ , or  $-R^{10}CO-(OCH_2CH_2)_n-OH$  provided that at least one of  $R^5$  and  $R^9$  is a hydroxyl group;  $R^{10}$  represents a  $C_{2-5}$  alkylene group;  $R^{11}$  represents a  $C_{1-8}$  alkyl group; and  $n$  is an integer of 2 to 20.

2. A photosensitive resin composition containing an alkali-soluble resin and a photosensitizer, which comprises at least one of N-phenyl-2H-benzotriazole compounds represented by the general formula (1) in claim 1.

3. The photosensitive resin composition according to claim 2, wherein the alkali-soluble resin is novolak resin, and the photosensitizer is a compound containing a quinonediazide group.